L Number	Hits	Search Text	DB	Time stamp
1	2	("6665562").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 15:21
2	2	("6772040").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 15:30
3	2	("6777654").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 15:46
4	5	("6700090").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 15:50
5	15234	plasma near processing	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 15:50
6	2052855	substrate or wafer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 15:51
7	1	modulat$ near period$ near ((high adj frequency)near voltage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 15:57
8	85	modulat$ near period$ and ((high adj frequency)near voltage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 16:00
9	119085	219/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 16:01
10	3	(plasma near processing) and (modulat$ near period$ and ((high adj frequency)near voltage)) and 219/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/10/31 16:01